

	Hits	Search Text	DBs
36	0	((resist or photoresist) same (PHS or polyhydroxystyrene or \$4hydroxystyrene\$4)) and ((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired) near6 thick\$5)) same transmiss\$3 same absorpt\$5 same (amount or percentage))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
37	1	((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired) near6 thick\$5)) same transmiss\$3 same absorpt\$5 same (amount or percentage))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
38	0	((resist or photoresist) same (PHS or polyhydroxystyrene or \$4hydroxystyrene\$4)) and (((expos\$4 or irradiat\$4 or illuminat\$4) near22 X\$3ray) or (secondary near6 electron)) and ((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired) near6 thick\$5))) and ((resist or photoresist or imaging) same (thickness) same transmiss\$3 same absorpt\$5 same (amount or percentage))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
39	13	((expos\$4 or irradiat\$4 or illuminat\$4) near22 X\$3ray) or (secondary near6 electron)) and ((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired) near6 thick\$5))) and ((resist or photoresist or imaging) same transmiss\$3 same absorpt\$5 same (thickness or layer or coating or amount or percentage))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
40	0	((resist or photoresist) same (PHS or polyhydroxystyrene or \$4hydroxystyrene\$4)) and (((expos\$4 or irradiat\$4 or illuminat\$4) near22 X\$3ray) or (secondary near6 electron)) and ((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired) near6 thick\$5))) and ((resist or photoresist or imaging) same transmiss\$3 same absorpt\$5 same (amount or percentage))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
41	3	((resist or photoresist) same (PHS or polyhydroxystyrene or \$4hydroxystyrene\$4)) and (((expos\$4 or irradiat\$4 or illuminat\$4) near22 X\$3ray) or (secondary near6 electron)) and ((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired) near6 thick\$5))) and ((resist or photoresist or imaging) same transmiss\$3 same absorpt\$5 same (thickness or layer or coating or amount or percentage))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
42	6	((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired) near6 thick\$5)) same (adjust\$4 or vary or var\$4) same (thickness or layer)) and ((resist or photoresist or imaging) same transmiss\$3 same absorpt\$5 same (thickness or layer or coating or amount or percentage))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
43	1	((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired) near6 thick\$5)) same (adjust\$4 or vary or var\$4) same (thickness or layer) same absorpt\$5) and ((resist or photoresist or imaging) same transmiss\$3 same (thickness or layer or coating or film)) and (((absorption near9 coefficient) or percentage or amount) same (photoresist or resist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
44	16	((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired) near6 thick\$5)) same (adjust\$4 or vary or var\$4) same (thickness or layer)) and ((resist or photoresist or imaging) same transmiss\$3 same (thickness or layer or coating or film)) and (((absorption near9 coefficient) or percentage or amount) same (photoresist or resist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB